

## INFORMATION DISCLOSURE STATEMENT

FORM PTO 1449 (modified)

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICELIST OF REFERENCES CITED BY APPLICANT(S)  
(Use several sheets if necessary)

Date Submitted to PTO: July 22, 2008

ATTY DOCKET NO.  
2006\_0772ASERIAL NO.  
10/581,256APPLICANT  
Mitsuhiro OKUNE et al.FILING DATE  
May 31, 2006GROUP  
1765

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	5,871,659	2/1999	Sakano et al.			
	AB	4,214,946	7/1980	Forget et al.			
	AC						
	AD						
	AE						
	AF						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	
	BA							
	BB							
	BC							
	BD							
	BE							

## OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

	CA	Supplementary European Search Report issued <u>June 11, 2008</u> in EP 04 81 9793, which is a foreign counterpart to the present application
	CB	Meint J. DE BOER et al., "Guidelines for Etching Silicon MEMS Structures Using Fluorine High-Density Plasmas at Cryogenic Temperatures", JOURNAL OF MICROELECTROMECHANICAL SYSTEMS IEEE Service Center, Piscataway, NJ, vol. 11, no. 4, August 1, 2002 (8/1/2002)
	CC	Seiji SAMUKAWA et al., "Effects of Discharge Frequency in Plasma Etching for Ultra large-Frequency Plasma Source for High-Performance Etching for Ultra large-Scale Integrated Circuits", JAPANESE JOURNAL OF APPLIED PHYSICS, Japan, Society of Applied Physics, Tokyo, Japan, vol. 39, no. 4A, Part 01, April 1, 2000 (4/1/2001)
	CD	

EXAMINER

DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.